

## United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/614,224	07/08/2003	Shingo Eguchi	0756-7174	7272
31780 7.	590 12/14/2004		EXAMINER	
ERIC ROBINSON		AKKAPEDDI, PRASAD R		
PMB 955	D 4 3 117 O/F		ART UNIT	PAPER NUMBER
21010 SOUTH				THERIOMEER
POTOMAC FA	ALLS, VA 20165		2871	

DATE MAILED: 12/14/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

			h
•	Application No.	Applicant(s)	
	10/614,224	EGUCHI ET AL.	
Office Action Summary	Examiner	Art Unit	-
	Prasad R Akkapeddi	2871	
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	correspondence add	ress
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be tire within the statutory minimum of thirty (30) day rill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed  /s will be considered timely. I the mailing date of this con ID (35 U.S.C. § 133).	nmunication.
Status			
Responsive to communication(s) filed on      This action is <b>FINAL</b> . 2b)⊠ This      Since this application is in condition for allowar closed in accordance with the practice under E	action is non-final. nce except for formal matters, pro		merits, is
Disposition of Claims			
4)⊠ Claim(s) <u>1-15</u> is/are pending in the application. 4a) Of the above claim(s) is/are withdray 5)□ Claim(s) is/are allowed. 6)⊠ Claim(s) <u>1-15</u> is/are rejected. 7)□ Claim(s) is/are objected to. 8)□ Claim(s) are subject to restriction and/or	vn from consideration.		
Application Papers			
9) The specification is objected to by the Examine 10) The drawing(s) filed on <u>08 July 2003</u> is/are: a) Applicant may not request that any objection to the Replacement drawing sheet(s) including the correction 11) The oath or declaration is objected to by the Examine	☑ accepted or b)☐ objected to be drawing(s) be held in abeyance. Selion is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFF	
Priority under 35 U.S.C. § 119			
<ul> <li>12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents</li> <li>2. Certified copies of the priority documents</li> <li>3. Copies of the certified copies of the prior application from the International Bureau</li> <li>* See the attached detailed Office action for a list of the certified copies of the prior application from the International Bureau</li> </ul>	s have been received. s have been received in Applicati ity documents have been receive ı (PCT Rule 17.2(a)).	ion No ed in this National S	stage
Attachment(s)			
<ol> <li>Notice of References Cited (PTO-892)</li> <li>Notice of Draftsperson's Patent Drawing Review (PTO-948)</li> <li>Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date <u>07/08/2003</u>.</li> </ol>	4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal F 6) Other:		152)

Art Unit: 2871

## **DETAILED ACTION**

## Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claims 1-3 are rejected under 35 U.S.C. 102(b) as being anticipated by Tamatani et al. (Tamatani) (U.S.Patent No. 5,893,625).

As to claim 1: Tamatani discloses a method of manufacturing a liquid crystal display device (title), having a pair of substrates (1a and 1b) sandwiching a seal pattern (2) (Fig. 1), injecting a liquid crystal between the pair of substrates through an opening of the seal pattern (3) and the opening (3) being positioned apart from a panel region (panel region being the where the display electrodes (16 and 17) and the pixel area are located (col. 4, lines 17-37). Tamatani also discloses a cutting position (severing) along a line (6) drawn between the opening (3) and the panel region as shown in (Fig. 1).

As to claims 2 and 3: Tamatani discloses a method of manufacturing a liquid crystal display device (title), with a liquid crystal interposed between a pair of substrates (1a and 1b), forming a seal pattern (2) with an opening (3) positioned apart from a panel region (panel region being the where the display electrodes (16 and 17) and the pixel area are located (col. 4, lines 17-37), bonding of the substrates (col.5, lines 6-7), a first severance treatment (cutting

Art Unit: 2871

line, 5), injection of the liquid crystal through the opening (3) and a second severance treatment (cutting line,6) along a line drawn between the opening (3) and the panel region as shown in (Fig. 1).

## Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims 4-6 are rejected under 35 U.S.C. 103(a) as being unpatentable over Tamatani in view of Nakahara et al. (Nakahara) (U.S.Patent No. 6,239,855).

As to claims 4-6: Tamatani teaches the use of cut lines (5 and 6) to cut the substrates. Although scribing and then cutting to severe the substrates commonly accomplish this, Tamatani does not explicitly teach that the method of severance treatment includes scribing to cut off.

Nakahara in disclosing a method of producing a liquid crystal display panel teaches the use of scribing and a break or cut off process (col. 2, lines 55-57, col. 4, lines 1-2 and elsewhere).

Therefore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to adapt the scribing and cut off process as disclosed by Nakahara to the liquid crystal display device of Tamatani in order

Art Unit: 2871

to prevent cell gap non-uniformity or a crack in the substrate from occurring in the severing process (col. 2, lines 35-38).

5. Claims 7-15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Tamatani in view of Hirakata et al. (Hirakata) (U.S.Patent Application Publication 2002/0024621)

As to claims 7-12: Tamatani's teachings include a broad category of liquid crystal materials and is not limited to smectic ferroelectric liquid crystals alone.

However, Tamatani is silent on the application to smectic ferroelectric liquid crystals.

Hirakata in disclosing a method of manufacturing liquid crystal display device, teaches the use of smectic ferroelectric liquid crystal (paragraphs 0002 and 0003).

Therefore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to adapt the smectic ferroelectric liquid crystals to the device of Tamatani in order for the ferroelectric liquid crystal to show hysteresis in a voltage transmittivity characteristic by making the cell gap thinner and also it is known to be a bistable material having a memory property. Hirakata also teaches that such a material characteristics are conventionally utilized and applied in the simple matrix method liquid crystal display device (paragraph 0009).

As to claims 13: Tamatani does not disclose monostabilization treatment.

Art Unit: 2871

Hirakata teaches the scribing (step 7) and then followed by monostabilization treatment (step 12) (Fig. 13), as recited in the instant claim.

Therefore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to adapt the monostabilization for eliminating bistable state or hysteresis seen in ferroelectric liquid crystals and obtaining an analog characteristic that fixes transmittivity by an electric field (paragraph 0015).

As to claims 14 and 15: Tamatani does not disclose monostabilization treatment.

Hirakata teaches the scribing (step 7) and then followed by monostabilization treatment (step 12) (Fig. 13), as recited in the instant claims.

Therefore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to adapt the monostabilization for eliminating bistable state or hysteresis seen in ferroelectric liquid crystals and obtaining an analog characteristic that fixes transmittivity by an electric field (paragraph 0015).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Prasad R Akkapeddi whose telephone number is 571-272-2285. The examiner can normally be reached on 7:00AM to 5:30PM M-Th.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Robert H Kim can be reached on 571-272-2293. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Page 6

Application/Control Number: 10/614,224

Art Unit: 2871

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Prasad R Akkapeddi, Ph.D Examiner Art Unit 2871

\*\*\* PRA

TARIFUR R. CHOWDHURY
PRIMARY EXAMINER